DOCKET NO.: 273504US0PCT/ab

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Shinji TANAKA, et al.

PATENT NO.: 7,470,824 GROUP: 1626

ISSUED: December 30, 2008 EXAMINER: KOSACK, JOSEPH R

FOR: ADAMANTANE DERIVATIVE AND PROCESS FOR PRODUCING THE SAME

REQUEST FOR CERTIFICATE OF CORRECTION

DIRECTOR OF THE UNITED STATES PATENT AND TRADEMARK OFFICE
ALEXANDRIA, VA 22313-1450

SIR:

The following is a Request for Certificate of Correction in Serial Number 10/540,547, now U.S. Patent Number 7,470,824.

In accordance with the provisions of Rule 322 of the Rules of Practice, which implement 35 USC 254, the U.S. Patent and Trademark Office is respectfully requested to issue a Certificate of Correction in the above-identified patent.

In light of the fact that the errors were the fault of the U.S. Patent and Trademark Office, no fees are required. The requested corrections are listed on FORM P.T.O. 1050.

Respectfully submitted,

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UNITED STATES PATENT AND TRADEMARK OFFICE

CERTIFICATE OF CORRECTION

PATENT NO. : **7,470,824**

DATED: **Dec. 30, 2008**

INVENTOR(S): **Tanaka et al.**

It is certified that an error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

On the title page, Item (87), the PCT information is incorrect. Item (87) should read:

--(87) PCT Pub. No.: **WO2004/058675**
PCT Pub. Date: **Jul. 15, 2004 --**

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Patent No. 7,470,824

No. of add'l copies
@ .30 per page

Français
1 of 1

Images

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(11) WO 2004/058675 **(13)** A1

(21) PCT/JP2003/016258

(22) 18 December 2003 (18.12.2003)

(25) Japanese **(26)** Japanese

(30) 2002-374659 25 December 2002 (25.12.2002) JP

(43) 15 July 2004 (15.07.2004)

(51)[7] **C07C 43/12**, 41/01, 49/517, 45/64

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(81) KR, US

(84) European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR)

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(57) An adamantane derivative represented by the general formula (I) or (II): (I) (II) wherein X represents halogeno; Y represents C_{1-10} alkyl, C_{1-10} haloalkyl, halogeno, or a heteroatom-containing group; R^1 to R^4 each independently represents hydrogen, halogeno, C_{1-10} alkyl, or C_{1-10} haloalkyl; m is an integer of 0 to 15; and n is an integer of 0 to 10; provided that in the general formula (I), the case where both of m and n are 0 and both of R^3 and R^4 are hydrogen is excluded. It is a novel adamantane derivative useful as a modifier for photoresist resins in the field of photolithography, a dry-etching resistance improver, an intermediate for agricultural chemicals and medicines, and other various industrial products.